

# Nikon A1R (Eastern Hill Precinct)

## INSTRUMENT SPECIFICATION SHEET



<b>Location</b>	Eastern Hill Precinct, Clinical Sciences Building level 1 Biofab3D laboratory						
<b>Stand</b>	Inverted Eclipse Ti1.0						
<b>Illumination</b>	<b>Transmitted</b>			<b>Fluorescence</b>			
	12V /100W Halogen lamp			Intensilight C-HGFI ( 130W Metal halide)			
<b>Filters</b>	<b>Name</b>	<b>Excitation</b>	<b>Dichroic</b>	<b>Emission</b>			
	DAPI	340-380	400	435-485	MBE41300		
	FITC	465-495	505	515-555	MBE44720		
	TxRed	540-580	595	600-660	Tex-Red-A –Basic-000		
	Cy3	535/50	565	610/75	Cy3-4040B-000		
<b>Lasers</b>	<b>Type</b>		<b>Wavelength</b>			<b>Maximum output</b>	
	Solid state laser cube		405			100mW	
	Solid state laser Sapphire		488			20mW	
	Solid state laser Sapphire		561			20mW	
	Solid state laser cube		635			25mW	
<b>Stage control</b>	Motorized XY stage						
<b>Objectives Specification</b>	<b>Magnification</b>	<b>Type</b>	<b>NA</b>	<b>Working distance nm</b>	<b>Coverslip Thickness</b>		<b>Resolution at 550nm (Glycerol mounted) nm</b>
4x PL FLUOR MRH00040	4x	Air	0.1	17100	170	-	Lateral: 2200 Axial:5230
10x PL FLUOR MRH00101	10x	Air	0.3	16000	170	DIC N1	Lateral: 733 Axial:1746
20x PL APO MRD70200	20x	Air	0.75	1000	170	DIC N2	Lateral: 293 Axial: 698
40x PL FLUO MRH01401	40x	Oil	1.3	200	170	DIC N2	Lateral:169 Axial: 402
60x PL FLUO MRD07601	60x	WI	1.2	270	150-190 collar	DIC N2	Lateral: 183 Axial: 436
100x PL APO MRD01901	100X	Oil	1.4	130	170	DIC	Lateral:157 Axial:374
*CFI PLAN APO 10XG MRD71120	10X	Water-Glycerol correction collar	0.5	2000	0-170	-	Lateral:440 Axial:1047
<b>Detectors</b>	<b>#</b>	<b>Type</b>		<b>Details</b>			
DU4	4	PMT					

A1-DUS	1	SD	32 channel PMT ( 400-720nm)
Diascopic detector unit	1	TPMT	Transmitted light detector
<b>Software</b>	NIS Elements AR 4.20		
<b>Holder</b>	Slides and microtiter plates		
<b>Applications</b>	Fixed samples		
<b>File Saving</b>	External drive		
<b>Extra features</b>	Resonant scanner , Perfect focus system, motorized stage		

\*This objective is kept out of the turret for access users need to attend a specific training